

U.S. Department of Commerce, Patent and Trademark				Atty. Docket No.		Application No.	
INFORMATION DISCLOSURE STATEMENT BY REQUESTOR				SENS.005US1		10/685,550	
				Applicant(s)		Conf. No.	
(Use several sheets if necessary)				Wayne G. Renken		4924	
				Filing Date		Group	
				October 14, 2003		2856	

U.S. Patent Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate

U.S. Published Patent Application Documents							
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
SS	1	2002/0078770	Jun. 27, 2002	Hunter			
SS	2	2002/0148307	Oct. 17, 2002	Jonkers			

Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
SS	3	WO 03/067183	Aug. 14, 2003	WIPO				

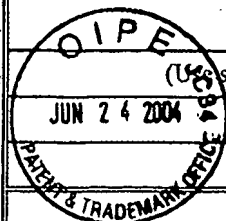
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		

Examiner	Sauif Shd	Date Considered	8/8/2007
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\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with your communication to applicant.

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88	1	RE.32,369	Mar. 10, 1987	Stockton et al.			
81	2	5,262,944	Nov. 16, 1993	Weisner et al.			
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	21	2002/0161557	Oct. 31, 2002	Freed			
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		Document	Date	Country	Class	Subclass	Yes	No
88	26	WO00/68986	Nov. 16, 2000	WIPO			Abstract	
88	27	EP 1014437 A2	Jun. 28, 2000	Europe				
88	28	WO02/17030A2	Feb. 28, 2002	WIPO				
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88	30	Prov. Pat. App. No. 60/285,613 filed 4/19/01; Freed et al.; "Firmware, Methods, Apparatus, and Computer Program Products for Wafer Sensors"						
88	31	Prov. Pat. App. No. 60/285,439 filed 4/19/01; Freed et al.; "Methods Apparatus, and Computer Program Products for Obtaining Data for Process Operation, Optimization, Monitoring, and Control"						
	32	Freed et al.; "Autonomous On-Wafer Sensors for Process Modeling, Diagnosis, and Control," IEEE Transactions on Semiconductor Manufacturing, Vol. 14, no. 3, Aug. 2001, pp 255-264.						
88	33	Freed; "Wafer-Mounted Sensor Arrays for Plasma Etch Processes", Dissertation, Univ. of CA. Berkeley, Fall 2001						
88	34	International Search Report, corresponding to PCT/US03/00751, 08/01/2003, 3 pages						
88	35	Baker et al.; "A Novel In Situ Monitoring Technique for Reactive Ion Etching Using a Surface Micromachined Sensor," IEEE Transactions on Semiconductor Manufacturing, Vol. 11, No. 2, May 1998, pp. 254-64.						
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